

Boron Carbide Coatings Deposited with HiPIMs

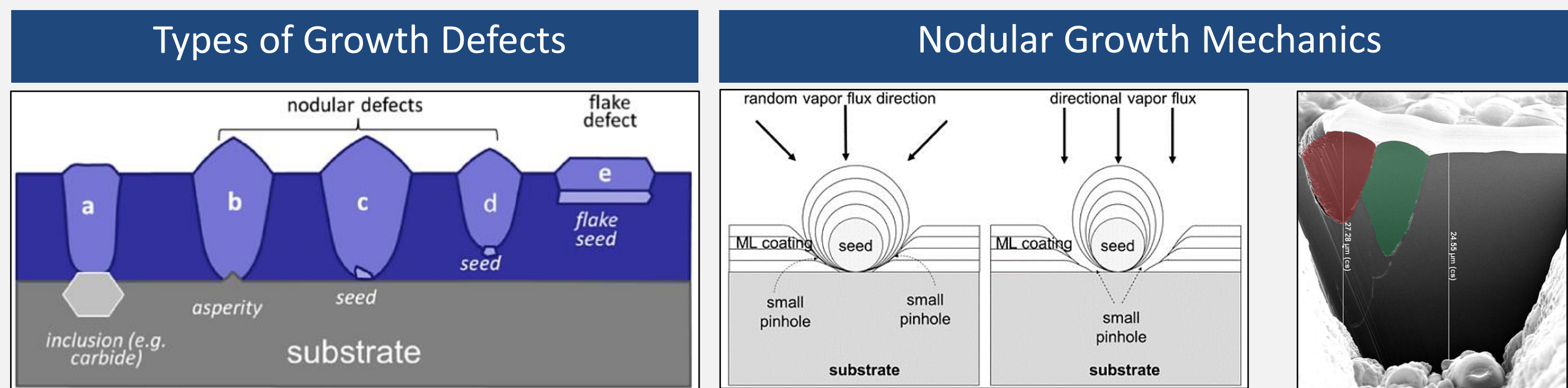
Abstract

- Boron carbide possesses many key properties that make it particularly well suited as a next generation ablator platform for inertial confinement fusion research.
- Fine control of growth modes including nodular growth defects, and columnar growth at oblique angles remains a challenge.
- These growth modes and defects result in non-uniformity in the ablator capsule in the which will significantly reduce implosion performance (Rayleigh-Taylor Instability).
- Here, we investigate the deposition of amorphous boron carbide films using high power impulse magnetron sputtering using a full faced erosion magnetron source.

Background

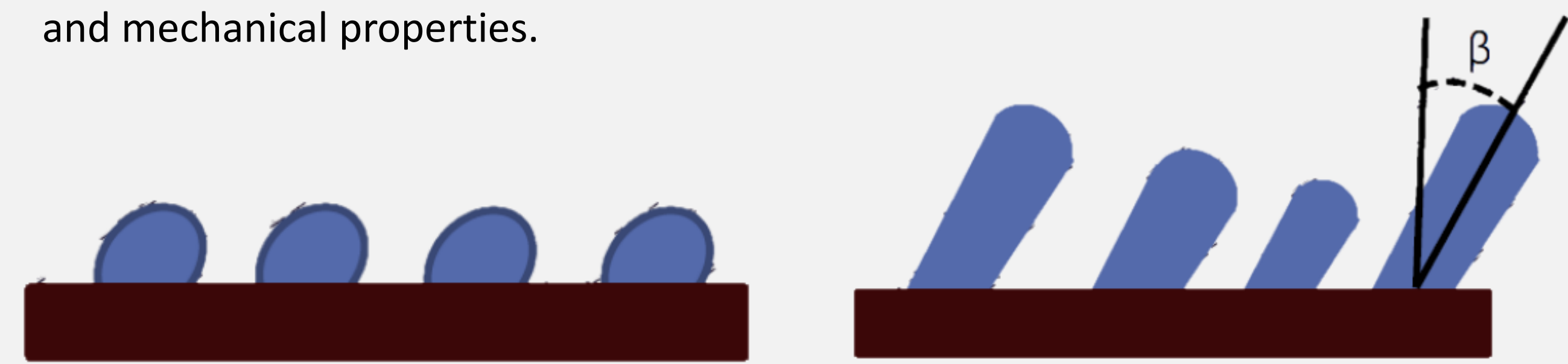
Nodular Growth Defects

- Nodular growth defects are irregularities that manifest from the film growth process.
- In PVD these typically come in the form of conical or parabolic nodular defects.
 - Particulate contamination on substrate
 - Discharge “arc” from target
 - Process stability
 - “Dusty Plasma”



Columnar Growth Modes

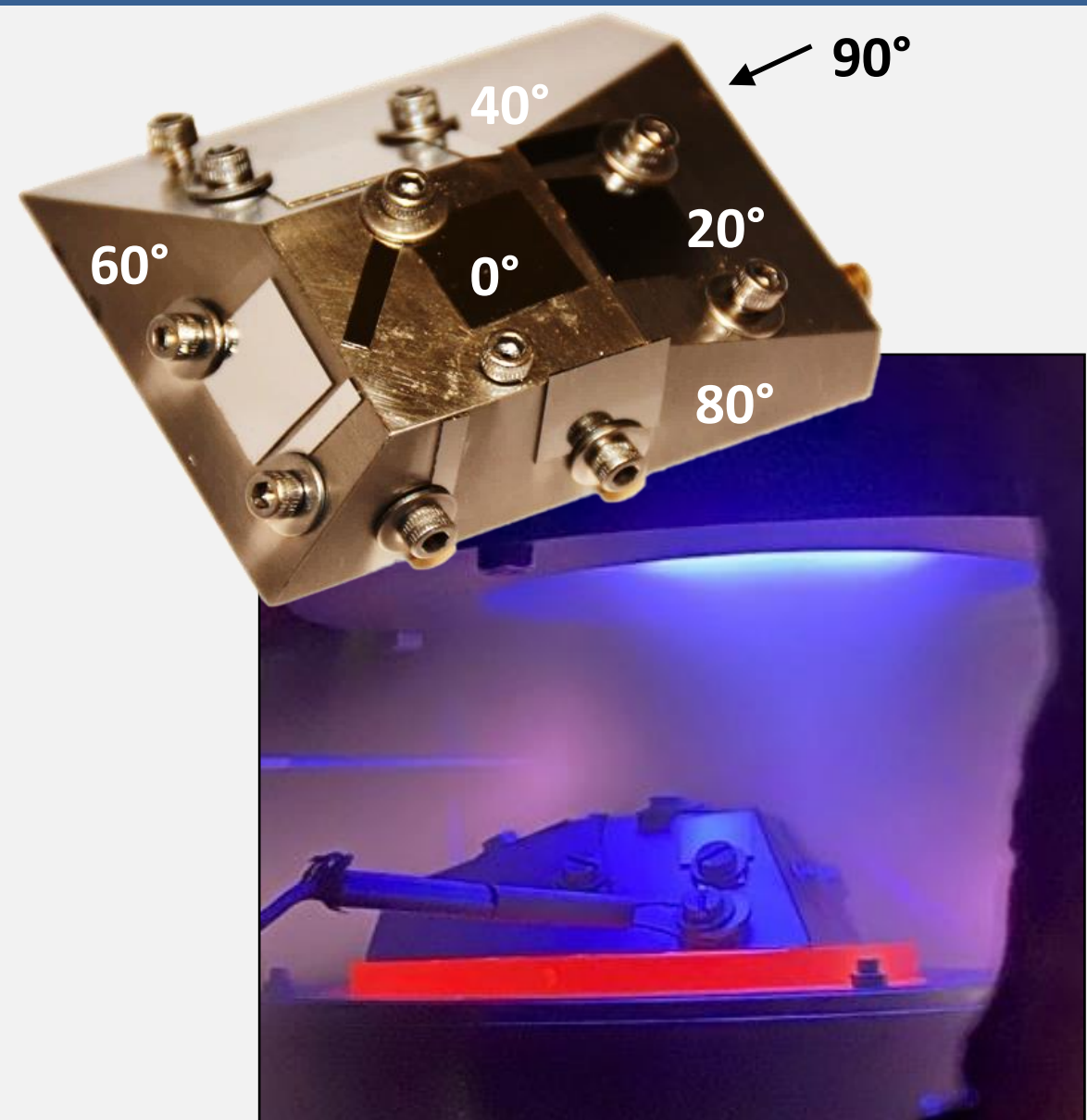
- Columnar growth is driven by shadowing effects due to the limited particle flux behind formed nuclei. Enhanced due to low adatom mobility.
- Columnar growth can increase porosity thereby leading to a reduction of film density and mechanical properties.



Summary box / Takeaway option if needed

Experimental Parameters

- Magnetron Type:** Full-faced erosion, MAK-gun
- Si Substrate Tilt Angles (°):** 0, 20, 40, 60, 80, 90
- Working Pressure (mTorr):** 20, 36
- Working Gases (4N):** Ar, 80 Ar/ 20 Ne
- Target to substrate distance ("):** 2
- Substrate Temperature (°C):** 450
- Power Types:** 13.56 MHz RF, HiPIMS
- Power:** 300 W RF, 500 W (avg.) HiPIMS
- Substrate Bias (V):** 0, -50 (HiPIMS only)



G.V. Taylor¹, S. Graiser¹, S.J. Shin¹, L.B. Bayu Aji¹, X.Lepro-Chavez¹, S.O. Kucheyev¹
¹Lawrence Livermore National Laboratory, Livermore, California 94550, USA

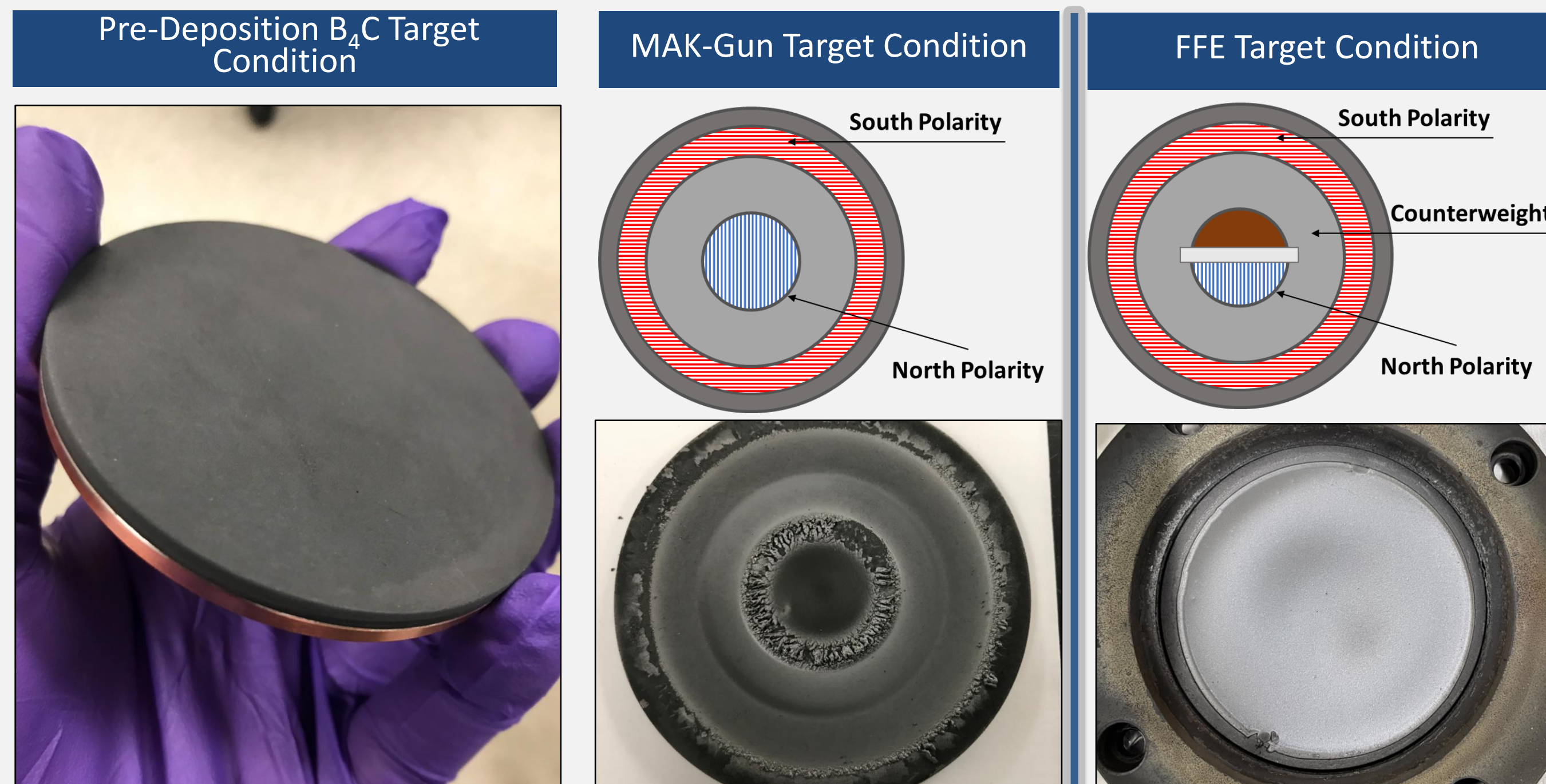
Reduction of Nodular Growth Defects

RF Deposition Parameters

Run #	Magnetron Rotation Speed (RPM)	Target Thickness (mm)	Sub. Temp (°C)	TSD (")	Pressure (mTorr)
1	100	5.9	450	2	27
2	100	5.7	450	2	36
3	200	4.7	450	2	36

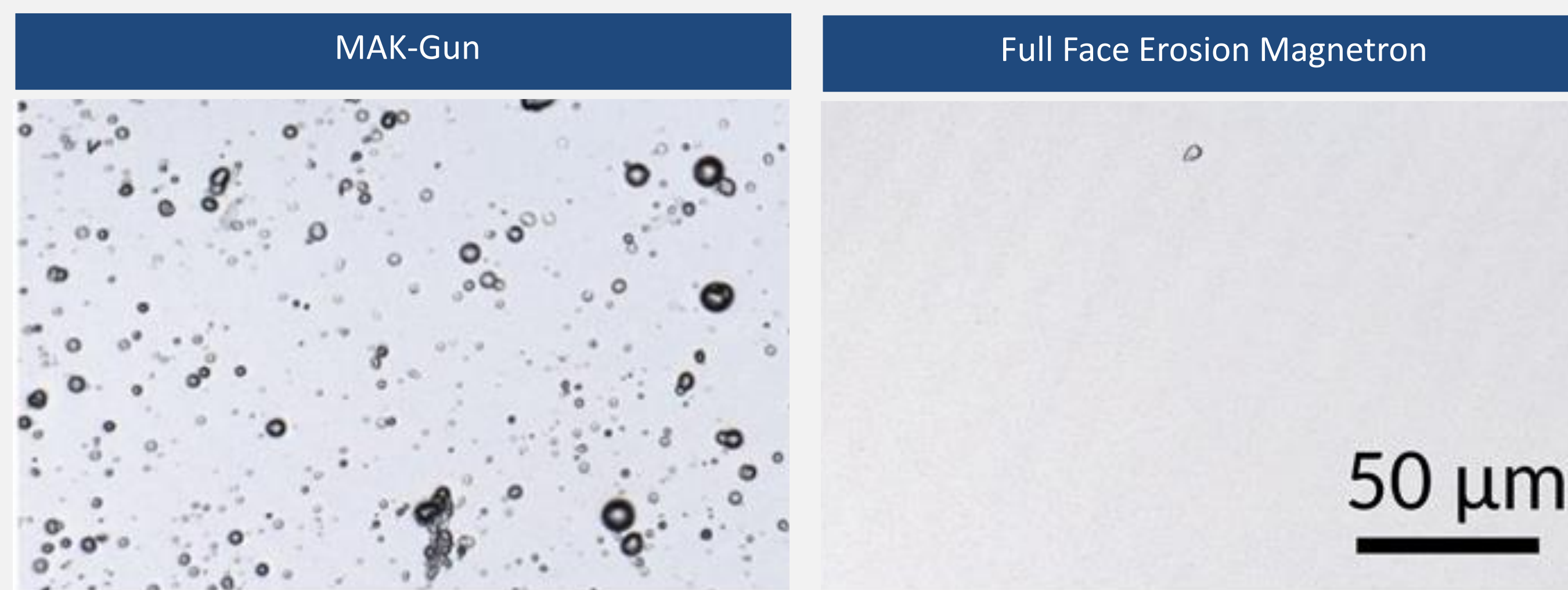
Residual stress was studied as a function of FFE Rotation speed and FFE target thickness.

Effect of Magnetron Design on Target Condition



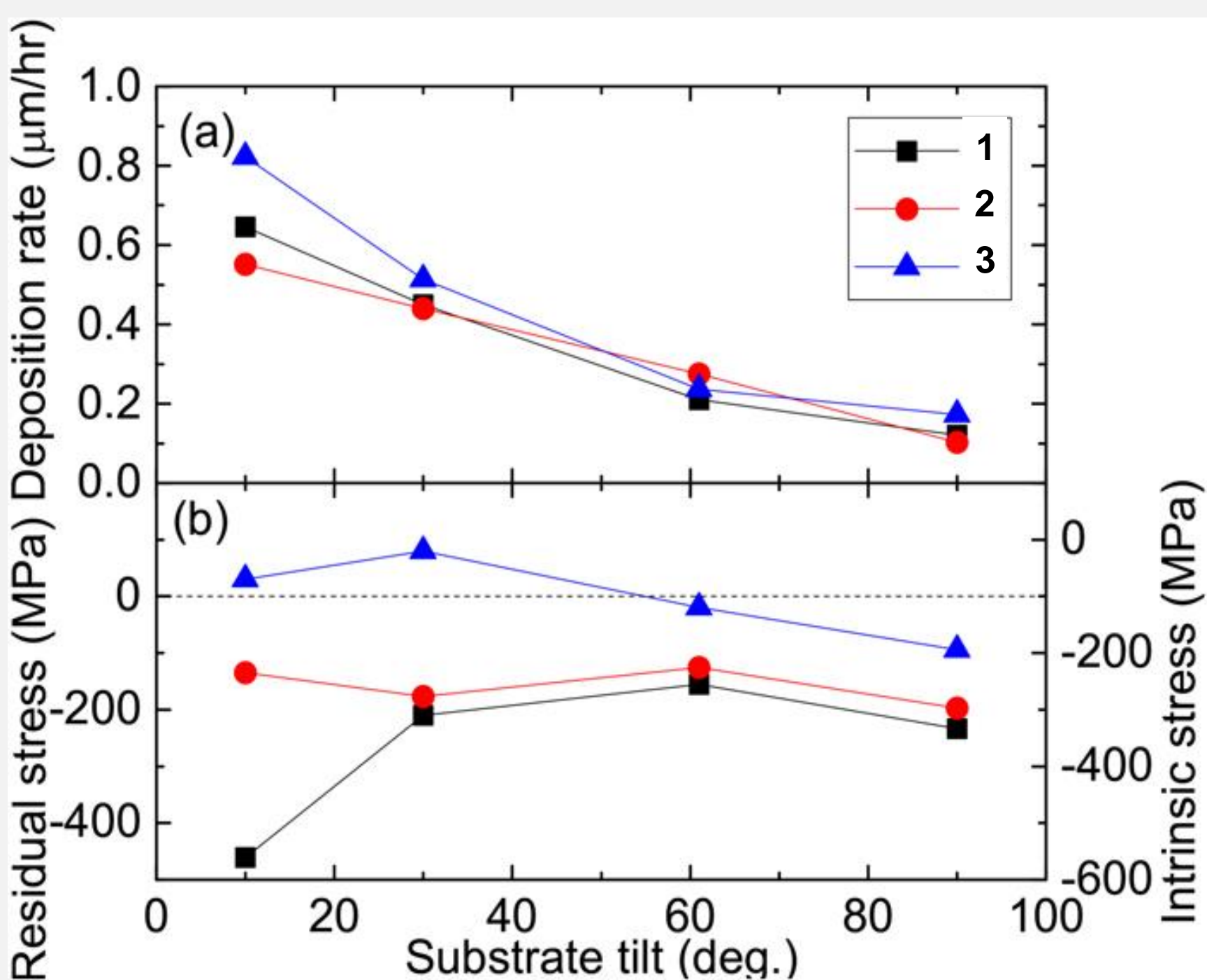
Redeposition of “dust” from plasma onto target virtually eliminated with FFE.

Nodule Defect Density



Confocal micrographs show the contrast in nodular defect density between MAK and FFE sources.

Residual Stress and Deposition Rate

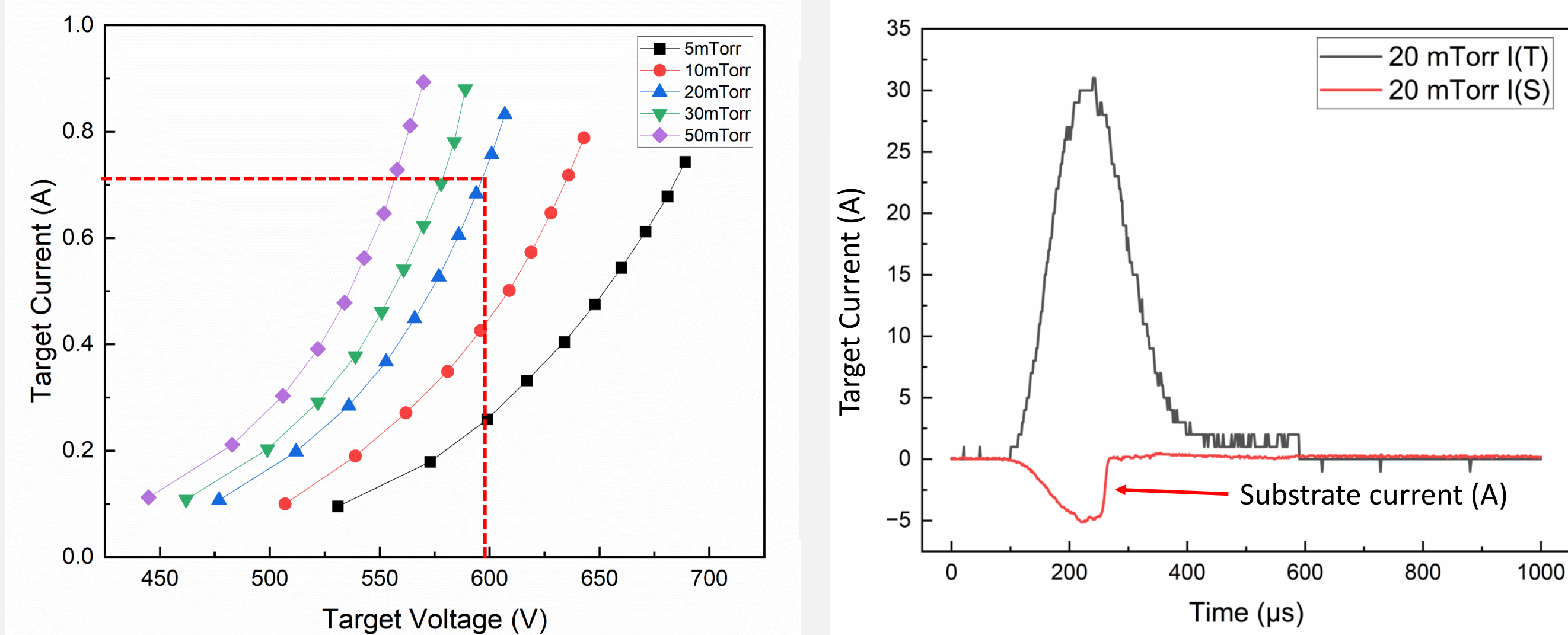


Additional Considerations

- Use CTE matching magnetron components and materials.
- Heating of adjacent surfaces to enhance B₄C adhesion.
- Operating and lower base pressures to reduce the occurrence of arcing and thereby droplets.
- Magnetron to substrate geometry and orientation.

Columnar Growth Modification with HiPIMs

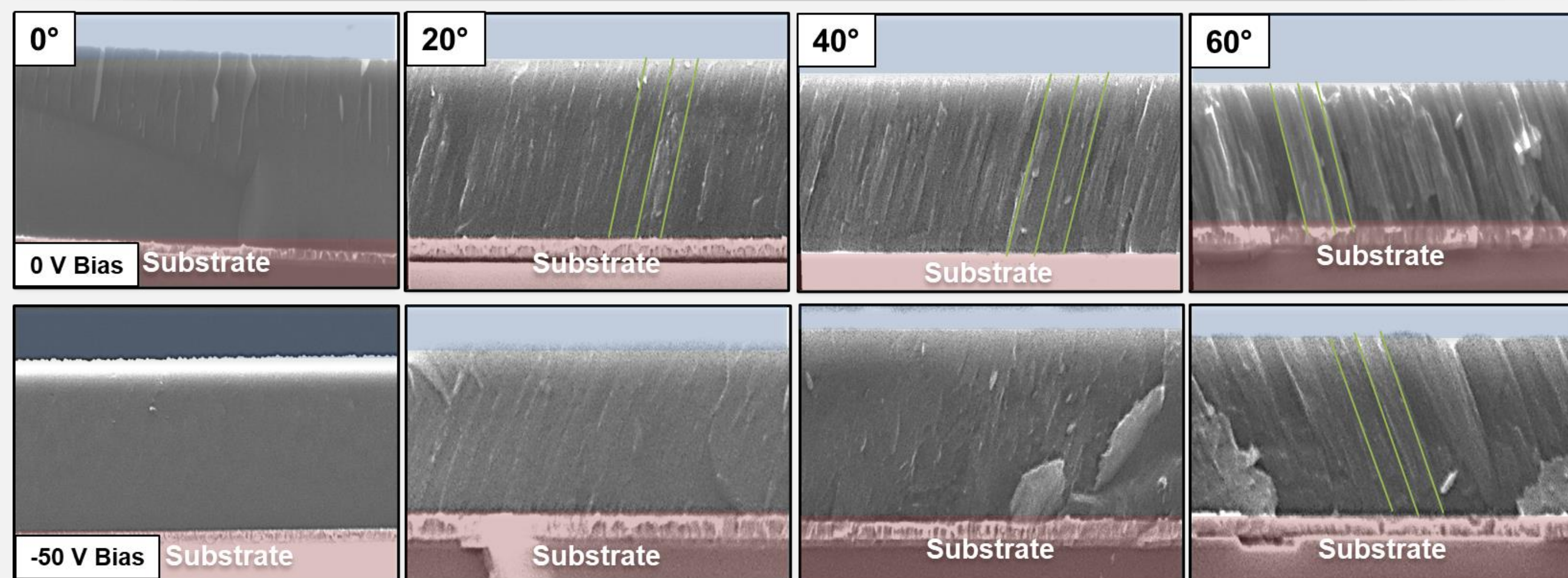
DC & HiPIMS I-V Characteristics



Higher working pressure results in higher target current for a given voltage

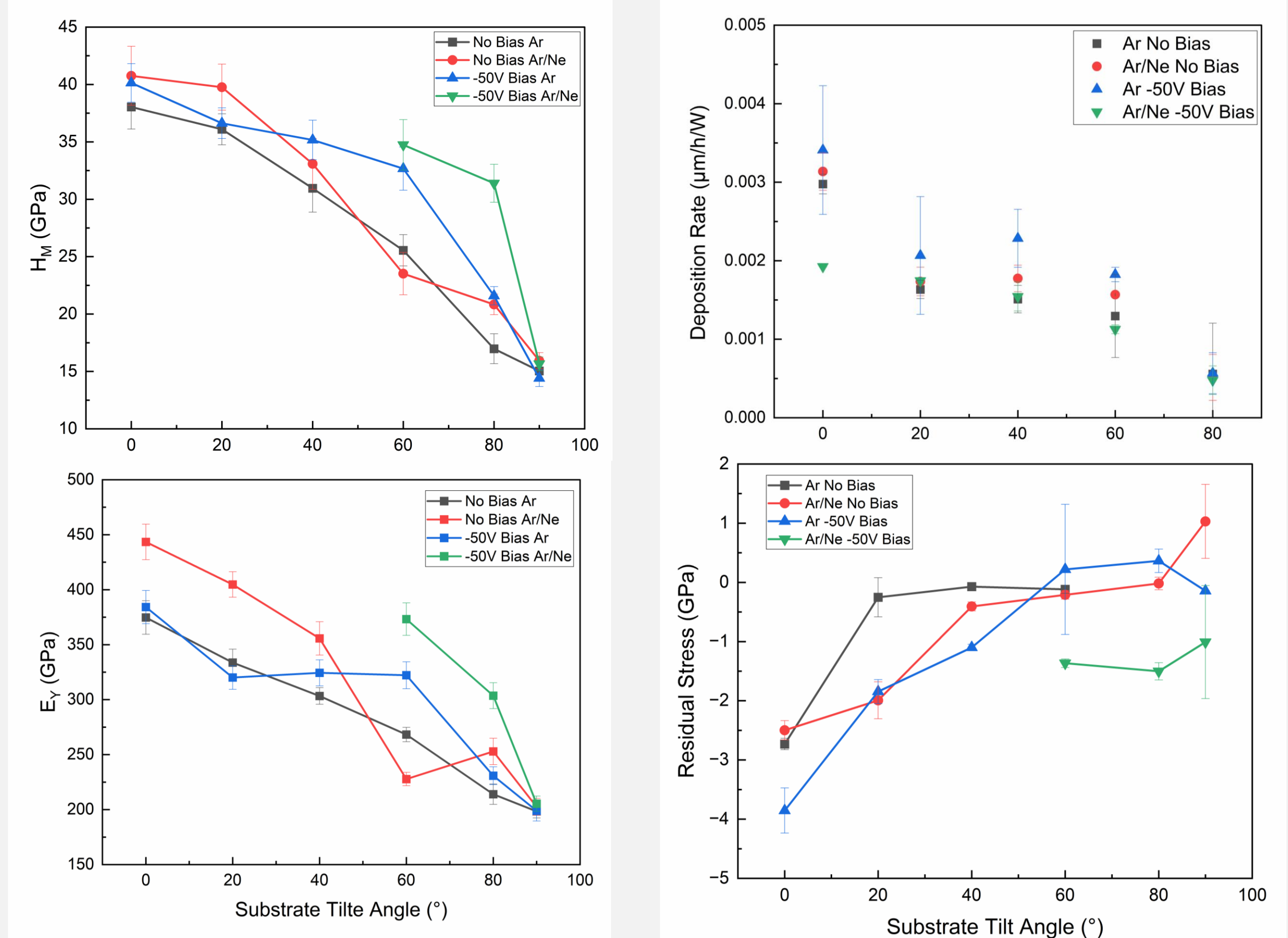
DC-IV Characteristics leveraged to achieve high peak target and substrate current with HiPIMS

Cross-sectional Microstructure



Redeposition of dust from plasma onto target significantly reduced with FFE.

HiPIMS B₄C Coating Properties



Conclusions and Future Work

- Reduction of nodular growth defects and suppression of columnar growth ($\leq 40^\circ$) can be accomplished using HiPIMS in tandem with FFE magnetron source.
- B₄C deposited using HiPIMS results in extremely hard coatings with high compressive residual stress.
- Further research is required to reduce residual stress of coatings.